

Title (en)
METHOD FOR DEPOSITING SILICON LAYERS

Title (de)
VERFAHREN ZUR ABSCHIEDUNG VON SILICIUMSCHICHTEN

Title (fr)
PROCÉDÉ DE DÉPÔT DE COUCHES DE SILICIUM

Publication
EP 2935645 A1 20151028 (DE)

Application
EP 13753307 A 20130816

Priority
• DE 102012108250 A 20120905
• EP 2013067150 W 20130816

Abstract (en)
[origin: WO2014037212A1] One embodiment of the invention concerns a method for depositing Si layers on substrates, there being deposited on a substrate in a chemical gas phase process layers of silicon from at least one precursor which is selected from halogenosilane compounds of the general empirical formulae Si_nX_{2n} and/or $\text{Si}_n\text{X}_{(2n+2)}$, in which X is a halogen and n is equal to or greater than 3.

IPC 8 full level
C23C 16/24 (2006.01)

CPC (source: EP)
C23C 16/24 (2013.01)

Citation (search report)
See references of WO 2014037212A1

Designated contracting state (EPC)
AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

Designated extension state (EPC)
BA ME

DOCDB simple family (publication)
DE 102012108250 A1 20140306; EP 2935645 A1 20151028; WO 2014037212 A1 20140313

DOCDB simple family (application)
DE 102012108250 A 20120905; EP 13753307 A 20130816; EP 2013067150 W 20130816